

Con. 6040-10.

( REVISED COURSE )

( 3 Hours )

[ Total Marks : 100

**N.B. :** (1) Question No. 1 is **compulsory**.

(2) Attempt any **four** questions out of question nos. 2 to 7.

(3) Draw **neat** diagrams wherever **required**.

1. (a) Compare Ion Implantation and Diffusion. 20  
 (b) Explain constant field scaling in MOS Device.  
 (c) Draw stick Diagram for CMOS Invertor.  
 (d) Implement function using CMOS  $f = \overline{ab + abc + a}$
2. (a) Explain Twin tub process in detail. 10  
 (b) Calculate the threshold voltage  $V_{TO}$  at  $V_{SB} = 0$ , for a polysilicon gate N-channel MOS transistor, with the following parameters : 10  
 Substrate doping density  $N_A = 10^{16} \text{ cm}^{-3}$   
 Polysilicon gate doping density  $N_D = 2 \times 10^{20} \text{ cm}^{-3}$ ,  
 Gate oxide thickness  $t_{ox} = 300 \text{ \AA}$  and  
 Oxide interface fixed charge density  $N_{ox} = 4 \times 10^{10} \text{ cm}^{-2}$ .
3. (a) Draw circuit of 2 input NAND gate, stick Diagram and Layout. 10  
 (b) For a CMOS invertor find the region of operation :— 10
  - (i)  $V_{in} < V_{th}$
  - (ii)  $V_{in} > C_{DD} + V_{tp}$
  - (iii)  $V_{in} = V_{IL}$
  - (iv)  $V_{in} = V_{IH}$
  - (v)  $V_{in} = \text{switching threshold.}$
4. (a) Compare resistive, Enhancement, Depletion load NMOS and CMOS invertor. 10  
 (b) Consider a CMOS invertor with the following parameters :— 10  
 NMOS  $V_{TO,n} = 0.6 \text{ V}$ ,  $\mu_n C_{ox} = 60 \text{ \mu A/V}^2$  and  $(W/L)_n = 8$   
 PMOS  $V_{TO,p} = -0.7 \text{ V}$ ,  $\mu_p C_{ox} = 25 \text{ \mu A/V}^2$  and  $(W/L)_p = 12$   
 Calculate the noise margins and the switching threshold ( $V_{th}$ ) of this circuit. The power supply voltage is  $V_{DD} = 3.3 \text{ V}$ .
5. (a) Write Verilog code of 1 Bit full adder using any style and instantiate it to design a 4 Bit full Adder. 10  
 (b) Explain the method to design 4:1 MUX using pass transistor logic. Draw complete stick diagram. 10

5. (a) Write Verilog code of 1 Bit full adder using any style and instantiate it to design a 4 Bit full Adder. 10
- (b) Explain the method to design 4:1 MUX using pass transistor logic. Draw complete stick diagram. 10
6. (a) Explain short channel effect in terms of :— 15
- (i) Velocity Saturation.
  - (ii) Mobility Degradation.
  - (iii) Channel Length Modulation.
  - (iv) Threshold Voltage.
  - (v) Hot Electron Effect.
- (b) An NMOS transistor with  $K = 20 \mu\text{A}/\text{V}^2$  and  $V_{TH} = 1.5\text{V}$  is operated at  $V_{GS} = 5\text{V}$  and  $I_D = 100 \mu\text{A}$ . Find  $V_{DS}$ . 5
7. Attempt any **three** :— 20
- (a) Compare Burried and Butting contact.
  - (b) Explain Latchup in CMOS and prevention.
  - (c) Compare Semi custom and Full custom design.
  - (d) Generate Verilog code for 4 Bit Shift Register.